

Abstract Submitted
for the MAR11 Meeting of
The American Physical Society

Prediction of a Low Band Gap Oxide Ferroelectric¹ DAVID SINGH, ORNL, BO XU, National University of Singapore, VALENTINO R. COOPER, ORNL, YUAN PING FENG, National University of Singapore — We report a first principles study of $\text{Bi}_6\text{Ti}_4\text{O}_{17}$ which is an alternate stacking of ferroelectric $\text{Bi}_4\text{Ti}_3\text{O}_{12}$ (BiT). We use the standard PBE GGA functional for the structure and polarization and a recently developed functional that yields accurate band gaps for the electronic structure. We find that this compound is ferroelectric although with a reduced polarization relative to BiT. Importantly, calculations of the electronic structure yield a band gap of approximately 1.4 eV. Therefore, we predict that this stacking is a low band gap oxide ferroelectric.

¹This work was supported by A*STAR (BX, YPF), the DOE, BES, Materials Sciences and Engineering (DJS, VRC, Ferroelectricity), and the ORNL LDRD Program (DJS, Electronic Structure).

David J. Singh
ORNL

Date submitted: 29 Nov 2010

Electronic form version 1.4